Search Notes	

Application/Control No.	Applicant(s)/Patent under Reexamination
09/484,303	AHN ET AL.
Examiner	Art Unit
W. David Coleman	2823

	SEARCHED			
Class	Subclass	Date	Examiner	
438	643 52	10/13/2005	WDC	
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INT	INTERFERENCE SEARCHED			
Class	Subclass	Date	Examiner	
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(INCLUDING SEARCH S	TRATEGY	
	DATE	EXMR
EAST 2.0.1 USPGPUBS; USPAT; JPO; EPO; Derwent; IBMTDB; IEEE; see search notes.		
Applicant clains an interconnect with a diffusion barrier formed after a lateral etching process.		
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